

Title (en)

DOPING MEDIA FOR THE LOCAL DOPING OF SILICON WAFERS

Title (de)

DOTIERMEDIEN ZUR LOKALEN DOTIERUNG VON SILIZIUMWAFERN

Title (fr)

SUBSTANCES DE DOPAGE DESTINÉES AU DOPAGE LOCAL DE TRANCHES DE SILICIUM

Publication

EP 2938761 A1 20151104 (DE)

Application

EP 13817883 A 20131218

Priority

- EP 12008660 A 20121228
- EP 13005734 A 20131210
- EP 13005735 A 20131210
- EP 13005736 A 20131210
- EP 13005737 A 20131210
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- EP 13817883 A 20131218

Abstract (en)

[origin: WO2014101989A1] The invention relates to a novel method for producing printable, high-viscous oxide media and to the use thereof in the production of solar cells.

IPC 8 full level

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Citation (search report)

See references of WO 2014101989A1

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DOCDB simple family (application)

EP 2013003838 W 20131218; CN 201380067938 A 20131218; EP 13817883 A 20131218; JP 2015550008 A 20131218; KR 20157020281 A 20131218; SG 10201704400Y A 20131218; SG 11201504937V A 20131218; TW 102148896 A 20131227; US 201314655857 A 20131218